

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) An exposure method in which a plurality of times of exposure is performed on a same photosensitive object wherein

a substantial wavelength of an exposure light in a space between a projection optical system, which projects said exposure light on said photosensitive object, and said photosensitive object is different in at least one exposure in said plurality of times of exposure from another exposure in said plurality of times of exposure, and a wavelength of said exposure light that enters said space for said at least one exposure is the same as a wavelength of said exposure light that enters said space for said another exposure, and

each of a plurality of areas on said photosensitive object is exposed by said plurality of times of exposure, and after said plurality of areas are exposed by one of said at least one exposure and said another exposure, said plurality of areas are exposed by the other of said at least one exposure and said another exposure,

wherein said exposure method is performed using a single exposure apparatus and said same photosensitive object is exposed with one illumination area, between said projection optical system and said photosensitive object, for said at least one exposure and said another exposure of said plurality of times of exposure.

2. (Canceled)

3. (Previously Presented) The exposure method according to Claim 1 wherein in said at least one exposure, said space is in a state filled with a predetermined liquid.

4. (Previously Presented) The exposure method according to Claim 3 wherein

in said another exposure, said space is in a state filled with another liquid that has a refractive index smaller than a refractive index of said predetermined liquid.

5. (Previously Presented) The exposure method according to Claim 3 wherein in said another exposure, said space is in a state filled with another liquid that has solubility to a specific material contained within a photosensitive agent of said photosensitive object lower than said predetermined liquid.

6. (Previously Presented) The exposure method according to Claim 3 wherein in said another exposure, said space is in a state not filled with liquid.

7. (Original) The exposure method according to Claim 6 wherein said at least one exposure is performed prior to said another exposure.

8. (Original) The exposure method according to Claim 6 wherein said at least one exposure is performed after said another exposure is performed.

9. (Currently Amended) The exposure method according to Claim 1 wherein a wavelength of ~~an~~ the exposure light ~~made to enter~~ that enters said projection optical system in said at least one exposure is different from a wavelength of an exposure light in ~~said another~~ a third exposure.

10. (Original) The exposure method according to Claim 1 wherein in said at least one exposure, a phase shift method is used.

11. (Previously Presented) A device manufacturing method including a lithography process wherein the exposure method of Claim 1 is performed to expose a photosensitive object a plurality of times.

12. (Currently Amended) An exposure method in which a plurality of times of exposure is performed on a same photosensitive object, said method comprising:

exposing, under a first exposure condition where a substantial wavelength of an exposure light in a space between an optical member and said photosensitive object is a first wavelength, said photosensitive object by said exposure light of said first wavelength; and

exposing, under a second exposure condition where a substantial wavelength of said exposure light in a space between said optical member and said photosensitive object is a second wavelength different from said first wavelength, said photosensitive object by said exposure light of said second wavelength, wherein

a wavelength of said exposure light that enters said space under said first exposure condition is the same as a wavelength of said exposure light that enters said space under said second exposure condition.

each of a plurality of areas on said photosensitive object is exposed by said plurality of times of exposure, and after said plurality of areas are exposed by one of the exposure under said first exposure condition and the exposure under said second exposure condition, said plurality of areas are exposed by the other of the exposure under said first exposure condition and the exposure under said second exposure condition, and

said exposure under said first exposure condition and said exposure under said second exposure condition are severally executed in a same exposure apparatus with one illumination area between said optical member and said photosensitive object.

13. (Canceled)

14. (Previously Presented) The exposure method according to Claim 12 wherein said exposure under said first exposure condition is an immersion exposure performed in a state where said space is filled with a predetermined liquid.

15. (Previously Presented) The exposure method according to Claim 14 wherein

said exposure under said second exposure condition is an immersion exposure performed in a state where said space is filled with another liquid that has a refractive index different from a refractive index of said predetermined liquid.

16. (Previously Presented) The exposure method according to Claim 15 wherein said predetermined liquid has a refractive index larger than the refractive index of said another liquid.

17. (Previously Presented) The exposure method according to Claim 14 wherein said exposure under said second exposure condition is an immersion exposure performed in a state where said space is filled with another liquid that has solubility to a specific material contained within a photosensitive agent of said photosensitive object different from said predetermined liquid.

18. (Original) The exposure method according to Claim 17 wherein said another liquid has solubility to said specific material contained within said photosensitive agent of said photosensitive object smaller than said predetermined liquid.

19. (Previously Presented) The exposure method according to Claim 14 wherein said exposure under said second exposure condition is a dry exposure performed in a state where said space is not filled with liquid.

20. (Original) The exposure method according to Claim 19 wherein said exposure under said first exposure condition is performed prior to said exposure under said second condition.

21. (Previously Presented) The exposure method according to Claim 19 wherein said exposure under said first exposure condition is performed after said exposure under said second exposure condition has been performed.

22. (Currently Amended) The exposure method according to Claim 12 wherein

said a wavelength of exposure light ~~made to enter~~that enters said optical member in said exposure under said first exposure condition is different from ~~the a~~ wavelength of exposure light that enters said optical member in ~~said an~~ exposure under ~~said second a third~~ exposure condition.

23. (Original) The exposure method according to Claim 12 wherein in said exposure under said first exposure condition, a phase shift method is used.

24-25. (Canceled)

26. (Previously Presented) A device manufacturing method including a lithography process wherein the exposure method of Claim 12 is performed to expose a photosensitive object a plurality of times.

27. (Currently Amended) An exposure apparatus that performs a plurality of times of exposure on a same photosensitive object, said apparatus comprising:

- a stage that holds said photosensitive object;
- a projection optical system that projects an exposure light on said photosensitive object;
- an adjustment unit that adjusts a substantial wavelength of said exposure light in a space between said projection optical system and said photosensitive object; and
- a control unit that controls said adjustment unit when exposing said photosensitive object a plurality of times so that in at least one exposure of said plurality of times, said substantial wavelength of said exposure light in said space is different from the substantial wavelength in another exposure,

wherein the exposure apparatus is a single exposure apparatus and said same photosensitive object is exposed with one illumination area, between said projection optical

system and said same photosensitive object, for said at least one exposure and said another ~~exposure-exposure, and~~

wherein a wavelength of said exposure light that enters said space is a same wavelength for said at least one exposure and for said another exposure, and said adjustment unit adjusts the substantial wavelength after the exposure light enters said space.

28. (Original) The exposure apparatus according to Claim 27 wherein

said adjustment unit comprises a liquid supply mechanism that supplies a predetermined liquid so that in a space between said projection optical system and said stage, at least a space between said projection optical system and said photosensitive object on said stage is filled with said liquid, whereby

said control unit controls said adjustment unit so that said liquid supply mechanism supplies said liquid to said space between said projection optical system and said photosensitive object on said stage in said at least one exposure, whereas in said another exposure said liquid supply mechanism does not supply said liquid to said space.

29. (Original) The exposure apparatus according to Claim 27 wherein

said adjustment unit comprises a liquid supply mechanism that supplies any one liquid of a plurality of types of liquid so that in a space between said projection optical system and said stage, at least a space between said projection optical system and said photosensitive object on said stage is filled with said liquid, whereby

said control unit controls said adjustment unit so that said liquid supply mechanism supplies a predetermined liquid of said plurality of types of liquid to said space between said projection optical system and said photosensitive object on said stage in said at least one exposure, whereas in said another exposure said liquid supply mechanism supplies a liquid different from said predetermined liquid to said space.

30. (Previously Presented) A device manufacturing method including a lithography process comprising

transferring a device pattern onto a photosensitive object by using the exposure apparatus according to Claim 27, and

performing further lithography processing.

31-39. (Canceled)

40. (Previously Presented) The exposure method according to claim 1, wherein throughout said plurality of times of exposure, said photosensitive object is exposed with said one illumination area.

41. (Previously Presented) The exposure method according to claim 12, wherein throughout said plurality of times of exposure, said photosensitive object is exposed with said one illumination area.

42. (Previously Presented) The exposure apparatus according to claim 27, wherein throughout said plurality of times of exposure, said photosensitive object is exposed with said one illumination area.